	Application No. Applicant(s)		
Notice of Allowability	10/678,317	578,317 DING, YI	
	Examiner	Art Unit	1
	Kevin M. Picardat	2822	124
The MAILING DATE of this communication appe All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RI	(OR REMAINS) CLOSED i or other appropriate comm GHTS. This application is and MPEP 1308.	n this application. If not include unication will be mailed in due o	ed course. <b>THIS</b>
1. This communication is responsive to papers filed on 26 Apr	<u>ril 2004</u> .		
2. ⊠ The allowed claim(s) is/are <u>1-13</u> .			
3. $igotimes$ The drawings filed on <u>03 October 2003</u> are accepted by the	e Examiner.		
4. Acknowledgment is made of a claim for foreign priority un a) All b) Some* c) None of the:  1. Certified copies of the priority documents have 2. Certified copies of the priority documents have 3. Copies of the certified copies of the priority documents have International Bureau (PCT Rule 17.2(a)).  * Certified copies not received:  Applicant has THREE MONTHS FROM THE "MAILING DATE" of noted below. Failure to timely comply will result in ABANDONMITHIS THREE-MONTH PERIOD IS NOT EXTENDABLE.  5. A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which give 6. CORRECTED DRAWINGS (as "replacement sheets") must (a) including changes required by the Notice of Draftsperson (b) including changes required by the attached Examiner's Paper No./Mail Date  [b] including indicia such as the application number (see 37 CFR 1.6 each sheet. Replacement sheet(s) should be labeled as such in the following required by the depose attached Examiner's comment regarding REQUIREMENT Formation in the depose attached Examiner's comment regarding REQUIREMENT Formation in the depose attached Examiner's comment regarding REQUIREMENT Formation in the depose attached Examiner's comment regarding REQUIREMENT Formation in the depose attached Examiner's comment regarding REQUIREMENT Formation in the depose attached Examiner's comment regarding REQUIREMENT Formation in the depose attached Examiner's comment regarding REQUIREMENT Formation in the depose attached Examiner's comment regarding REQUIREMENT Formation in the depose attached Examiner's comment regarding REQUIREMENT Formation in the depose attached Examiner's comment regarding REQUIREMENT Formation in the depose attached Examiner's comment regarding REQUIREMENT Formation in the depose attached Examiner's comment regarding REQUIREMENT Formation in the depose attached Examiner's comment regarding Requirement formation in the depose attached Examiner's comment regarding Requirement formation in the depose attached Examiner's comment regarding Require	been received.  been received in Application currents have been received of this communication to file ENT of this application.  Itted. Note the attached EX as reason(s) why the oath of the submitted.  It be submitted.  It is Amendment / Comment of the header according to 37 CF is it of BIOLOGICAL MAT	on No  Indicated in this national stage applicated in this national stage applicated in this national stage applicated in the requirement of the drawings in the front (not the FR 1.121(d).  ERIAL must be submitted. Note the stage of the drawings in the submitted. Note the submitted in the submitted.	uirements  OTICE OF  back) of
Attachment(s)  1. ☑ Notice of References Cited (PTO-892)  2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)  3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/08 Paper No./Mail Date 4-26-04,12-22-03  4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material	6. ☐ Interview S Paper No 3), 7. ☐ Examiner's	nformal Patent Application (PTC) ummary (PTO-413), /Mail Date Amendment/Comment Statement of Reasons for Allow	·
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		Kovin M. Pisan Primary Exemi	

U.S. Patent and Trademark Office PTOL-37 (Rev. 1-04) The following is an examiner's statement of reasons for allowance: None of the prior art teaches or suggests a method for manufacturing an integrated circuit including removing material from at least the top exposed portion of each sidewall of each of the dielectric region, to recess the top portion of the sidewall laterally away from the adjacent first portion of the floating gate, forming a second conductive layer over the one or more first areas, the second conductive layer contacting the first conductive layer and providing a second portion of the floating gate for each nonvolatile memory cell, the second conductive layer abutting the top recessed sidewall portions of the dielectric regions.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Kevin M. Picardat whose telephone number is 571-272-1841. The examiner can normally be reached on Monday-Thursday 7:00-5:30.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Amir Zarabian can be reached on 571-272-1852. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Kevin M. Picardat Primary Examiner Art Unit 2822